

<b>Notic of R f rences Cit d</b>	Application/Control No. 10/073,877		Applicant(s)/Patent Under Reexamination WATANABE ET AL.	
	Examiner Maria Guerrero		Art Unit 2822	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,441,912	08-1995	Tsukiji et al.	438/40
	B	US-5,452,315	09-1995	Kimura et al.	372/46
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Adachi et al. "Chemical Etching of InGaAsP/InP DH Wafer", March 1982, Journal of the Electrochemical Society, Vol. 129, Pages 1053-1062.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.